MULTI-LATTICE MULTI-RESOLUTION COMBINATION MOLD



This versatile multi-purpose design combines three most commonly needed lattice types: linear, square and hexagonal. The combination enables researchers to test the effects of different lattice types as well as lattice periods on the same substrate in a single experiment, thus saving valuable time and resources. The design has been optimized to cover the widest possible range of research demands based on customer feedback. The patterns are made with Eulitha's revolutionary PHABLE[™] technology. Optimized silicon and quartz etching yields patterns with a slight positive slope that facilitates the imprint process.

(MHSL400-800 on a 4" Si substrate)

Our standard molds are intended for research and development work. Please contact us for larger areas, special substrates, or high-volume applications.

Nanophotonics Photovoltaics Transmission and reflection gratings Nanoimprint development Epitaxial growth templates Self-assembly templates



(Layout of MHSL400-800 showing pattern periods. Drawing not to scale)

- * Substrate: up to 4-inch diameter Si or fused silica
- ** Feature height: customer selectable up to 400nm for Si and up to 150nm for fused silca
- *** Anti-stick coating optional



400 nm period square



600 nm period hexagonal



400 nm period linear

